



# MICROSTRUCTURE MORPHOLOGY OF BICONTINUOUS NANOCOMPOSITES THIN-FILMS DURING PHYSICAL VAPOR DEPOSITION (PVD)

**REMI DINGREVILLE, CINT, SANDIA NATIONAL LABORATORIES**

# MULTI-DISCIPLINARY & COLLABORATIVE RESEARCH



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- **Funding**



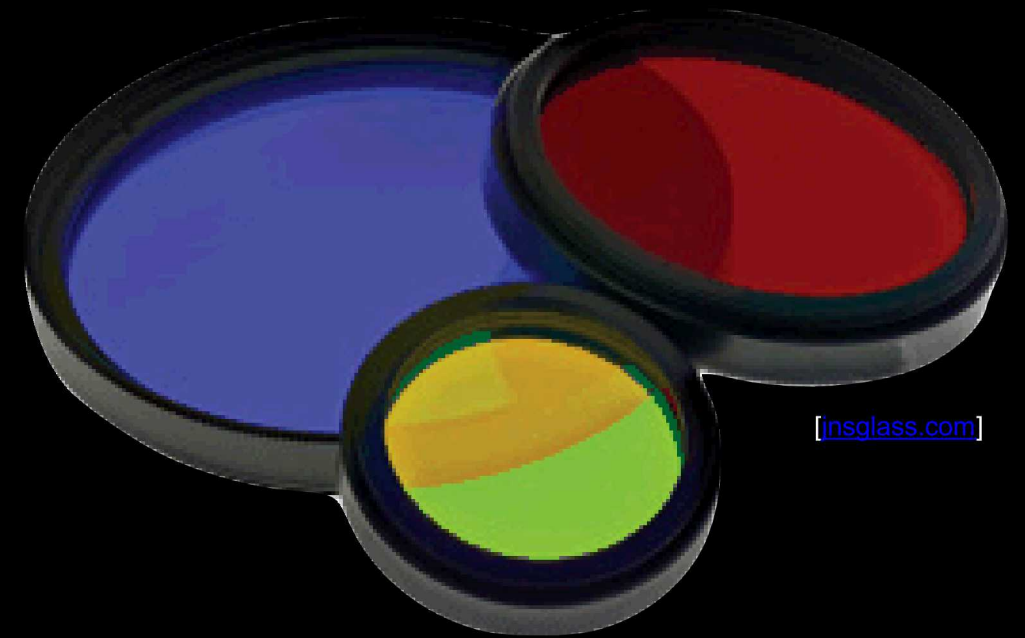


# WE USE THIN-FILM COATINGS TO ACHIEVE TARGETED TECHNOLOGICAL FUNCTIONALITIES

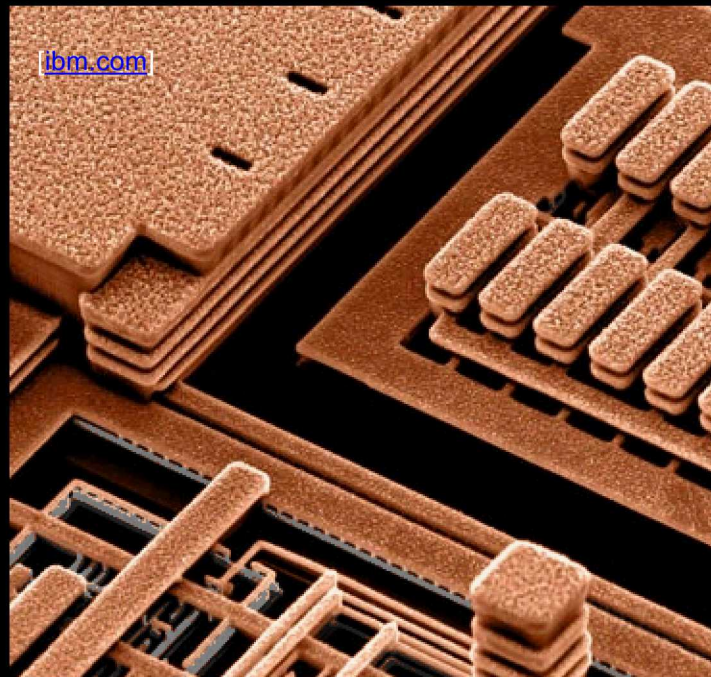
Decorative



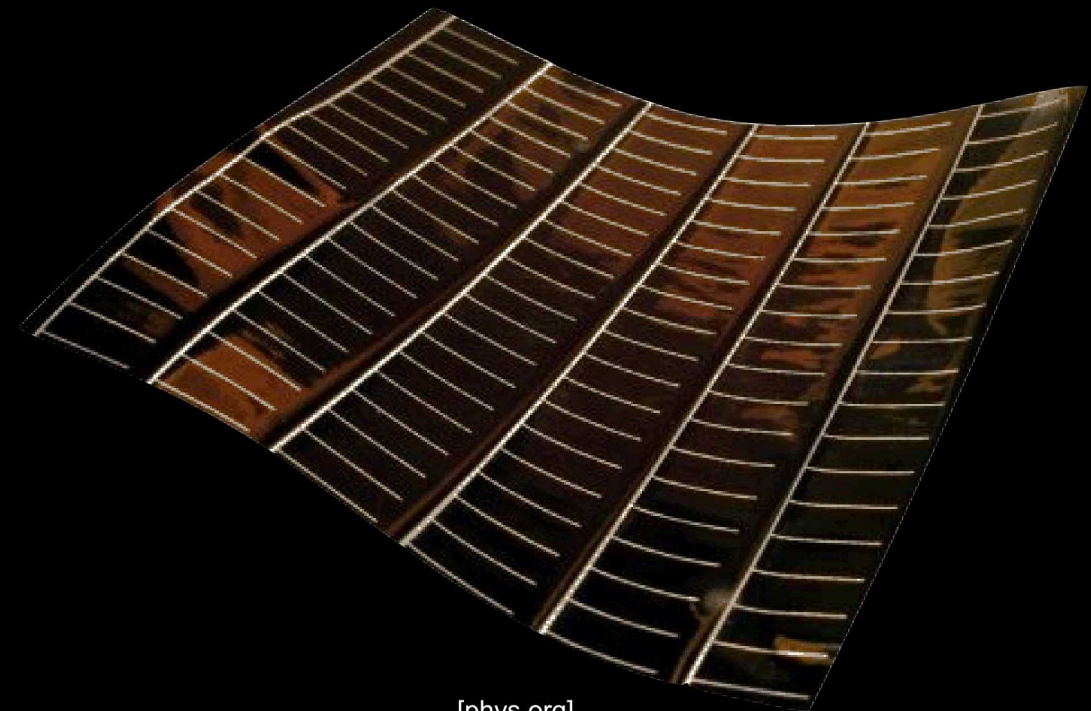
Optical



Mechanical



Microelectronic



Photovoltaic



# THE HISTORY OF PVD IS CLOSELY LINKED TO THE DISCOVERY OF ELECTRICITY AND MAGNETISM

VIII. *Experimental Researches in Electricity.—Thirteenth Series.* By MICHAEL FARADAY, Esq., D.C.L. F.R.S. Fullerian Prof. Chem. Royal Institution, Corr. Memb. Royal and Imp. Acadd. of Sciences, Paris, Petersburg, Florence, Copenhagen, Berlin, &c. &c.

Received February 22,—Read March 15, 1838.

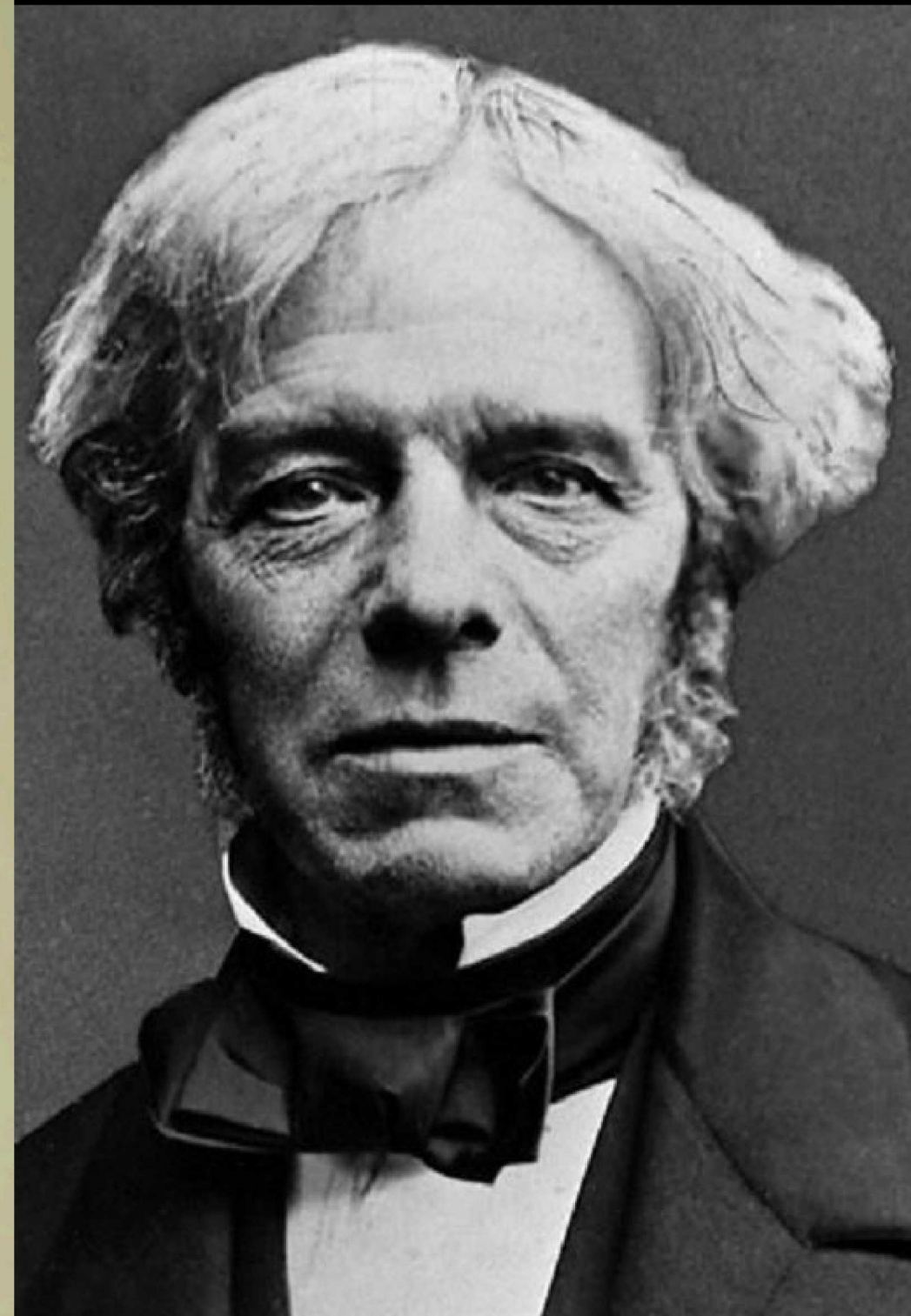
§. 18. *On Induction (continued).* ¶ ix. *Disruptive discharge (continued)—Peculiarities of positive and negative discharge either as spark or brush—Glow discharge—Dark discharge.*—¶ x. *Convection, or carrying discharge.* ¶ xi. *Relation of a vacuum to electrical phenomena.* §. 19. *Nature of the electrical current.*

¶ ix. *Disruptive discharge (continued).*

1480. LET us now direct our attention to the general difference of the positive and negative disruptive discharge, with the object of tracing, as far as possible, the cause of that difference, and whether it depends on the charged conductors principally, or on the interposed dielectric; and as it appears to be great in air and nitrogen (1476.), let us observe the phenomena in air first.

1481. The general case is best understood by a reference to surfaces of considerable size rather than to points, which involve (as a secondary effect) the formation of currents (1562.). My investigation, therefore, was carried on with balls and terminations of different diameters, and the following are some of the principal results.

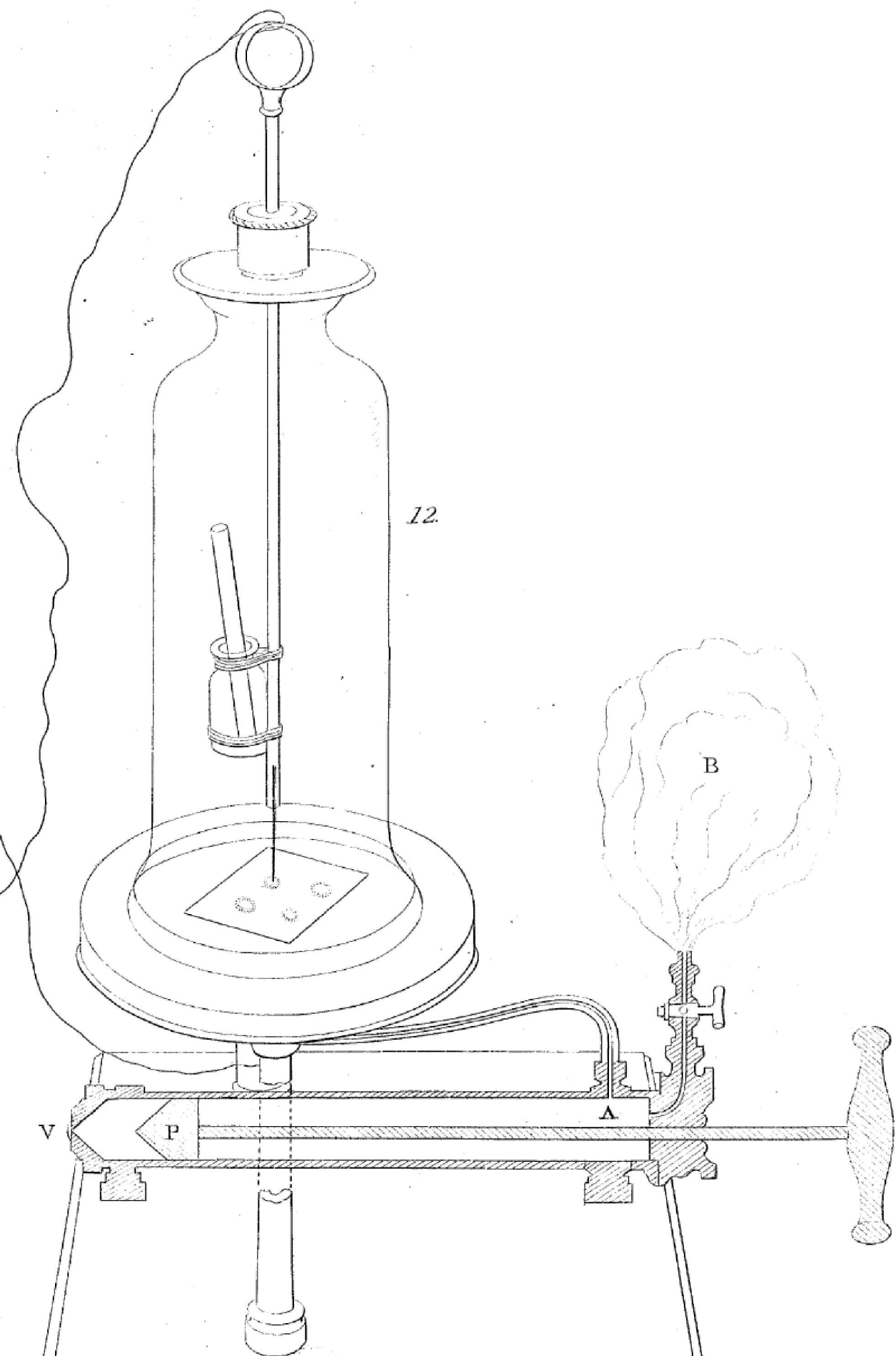
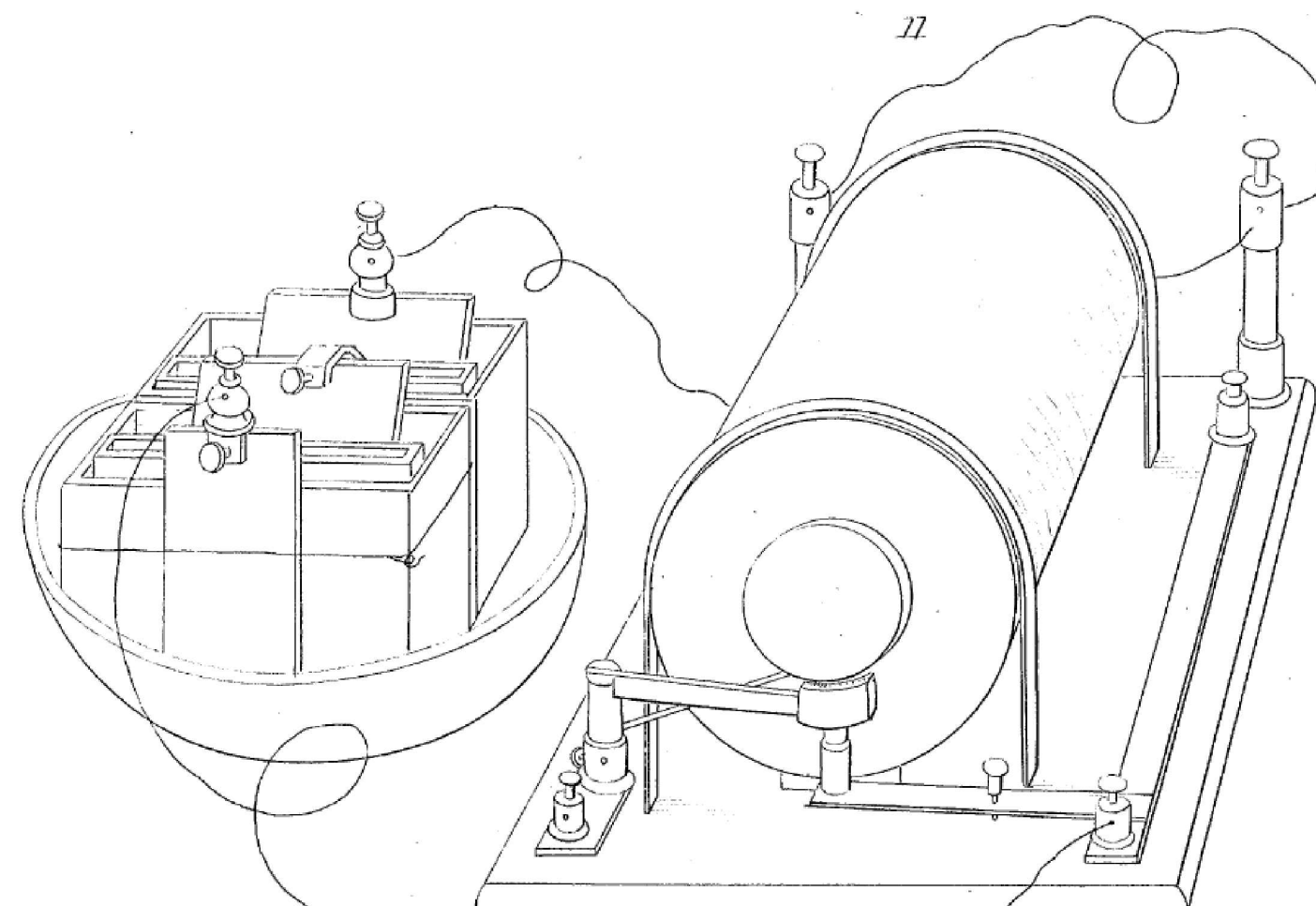
1482. If two balls of very different dimensions, as for instance one, half an inch, and the other three inches, in diameter, be arranged at the ends of rods so that either can be electrified by a machine and made to discharge by sparks to the other, which is at the same time uninsulated; then, as is well known, far longer sparks are obtained







**William Robert  
Grove**



*Phil. Trans. MDCCCLIII. Plate VIII. p101*

T. A. EDISON.

ART OF PLATING ONE MATERIAL WITH ANOTHER.

No. 528,147.

Patented Sept. 18, 1894.

Fig 1.

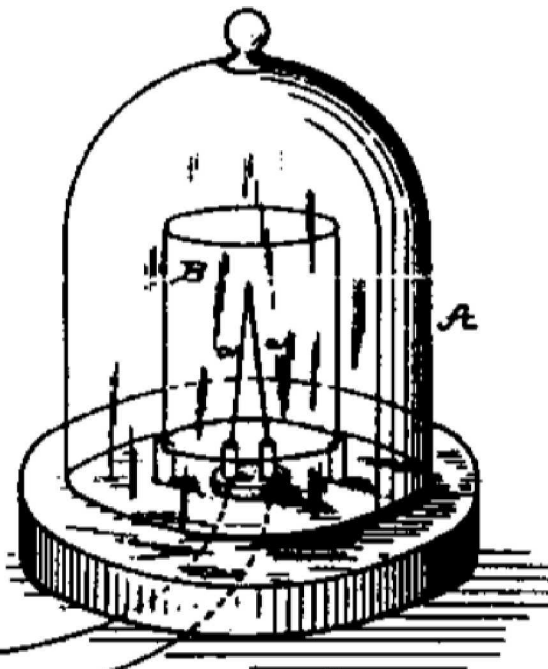
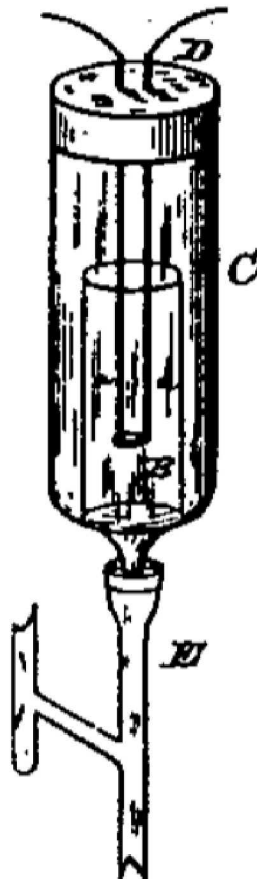


Fig 2.

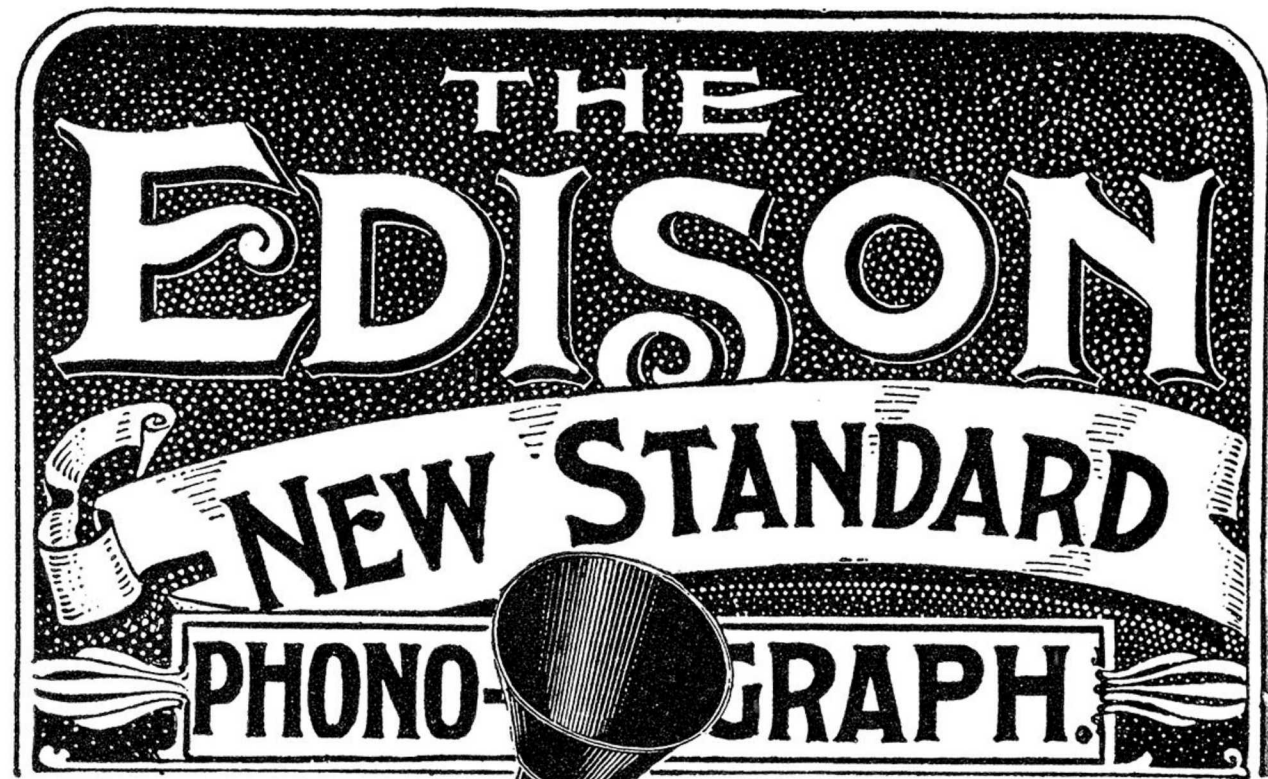


WITNESSES:

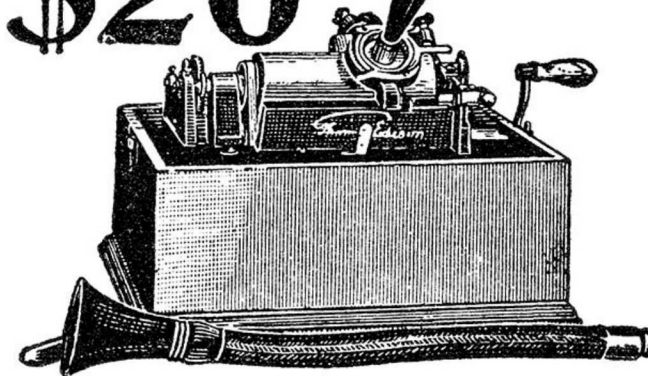
*Ed. R. Sanford*  
*W. L. Lacey*

INVENTOR:

*Thomas A. Edison*  
*By Rich. A. Dyer*  
*Atty.*



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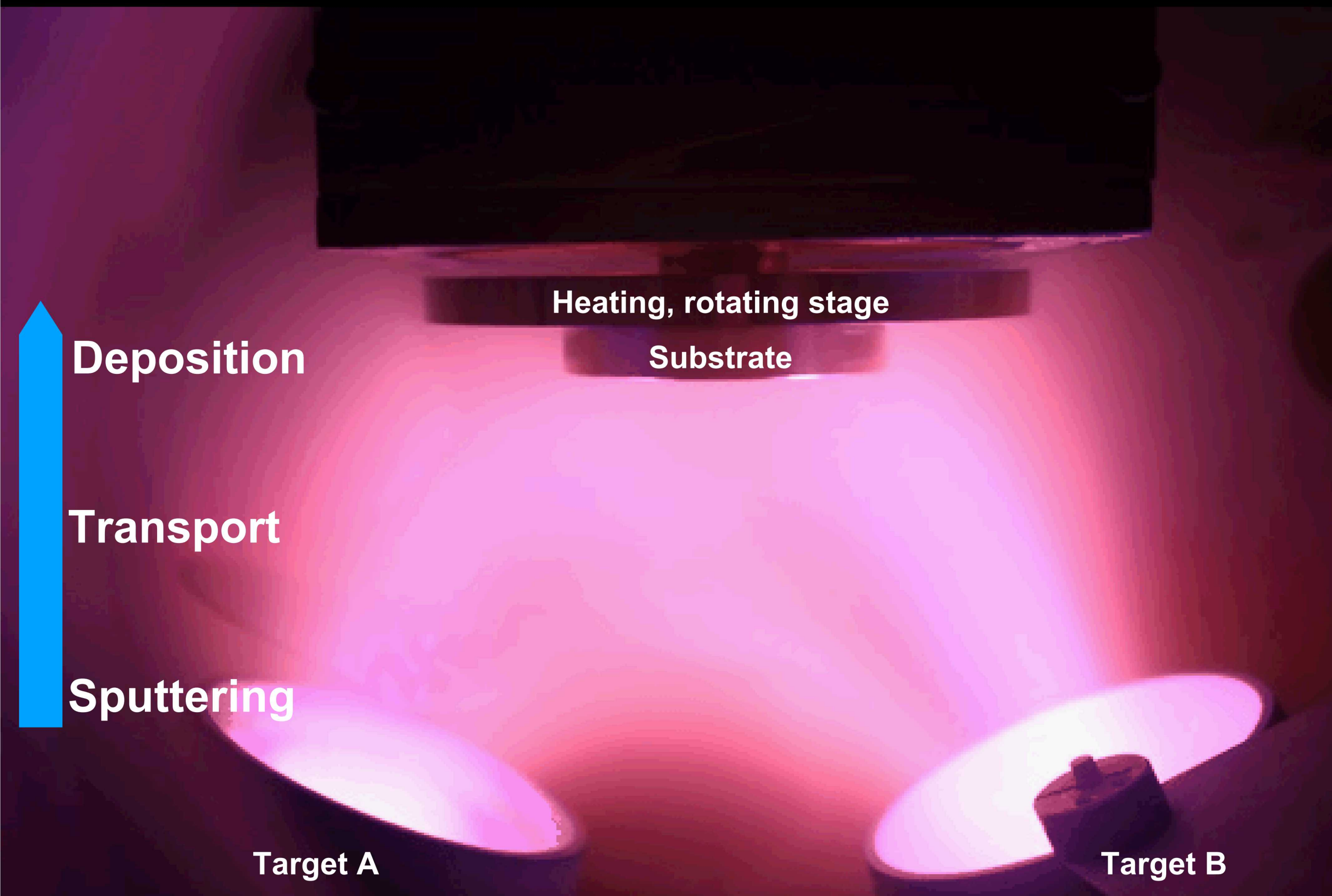
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# PVD IS A SYNTHESIS ROUTE TO DEPOSIT AND ENGINEER THIN-FILMS ONE ATOM AT A TIME

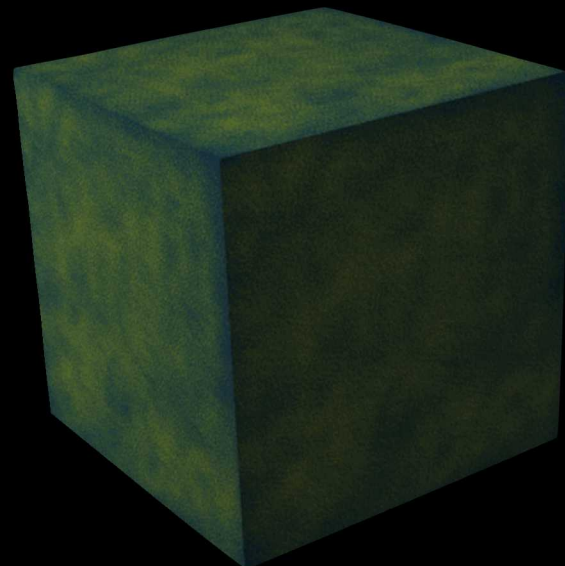




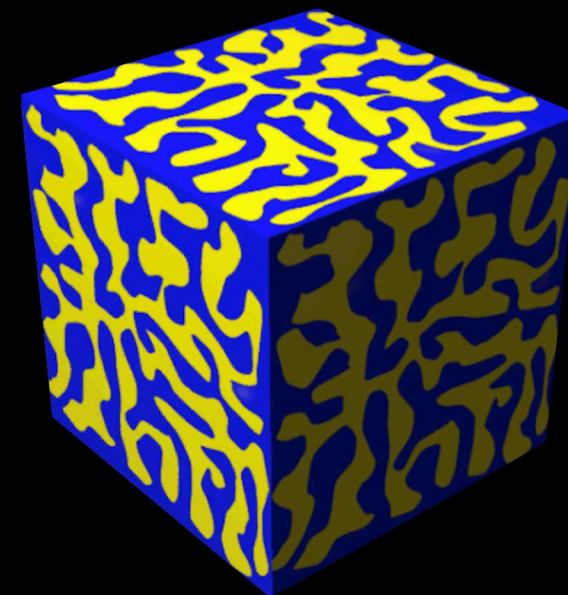
# DIFFERENT PVD SYNTHESIS ROUTES ENABLE (SOME) CONTROL OF THE MORPHOLOGY



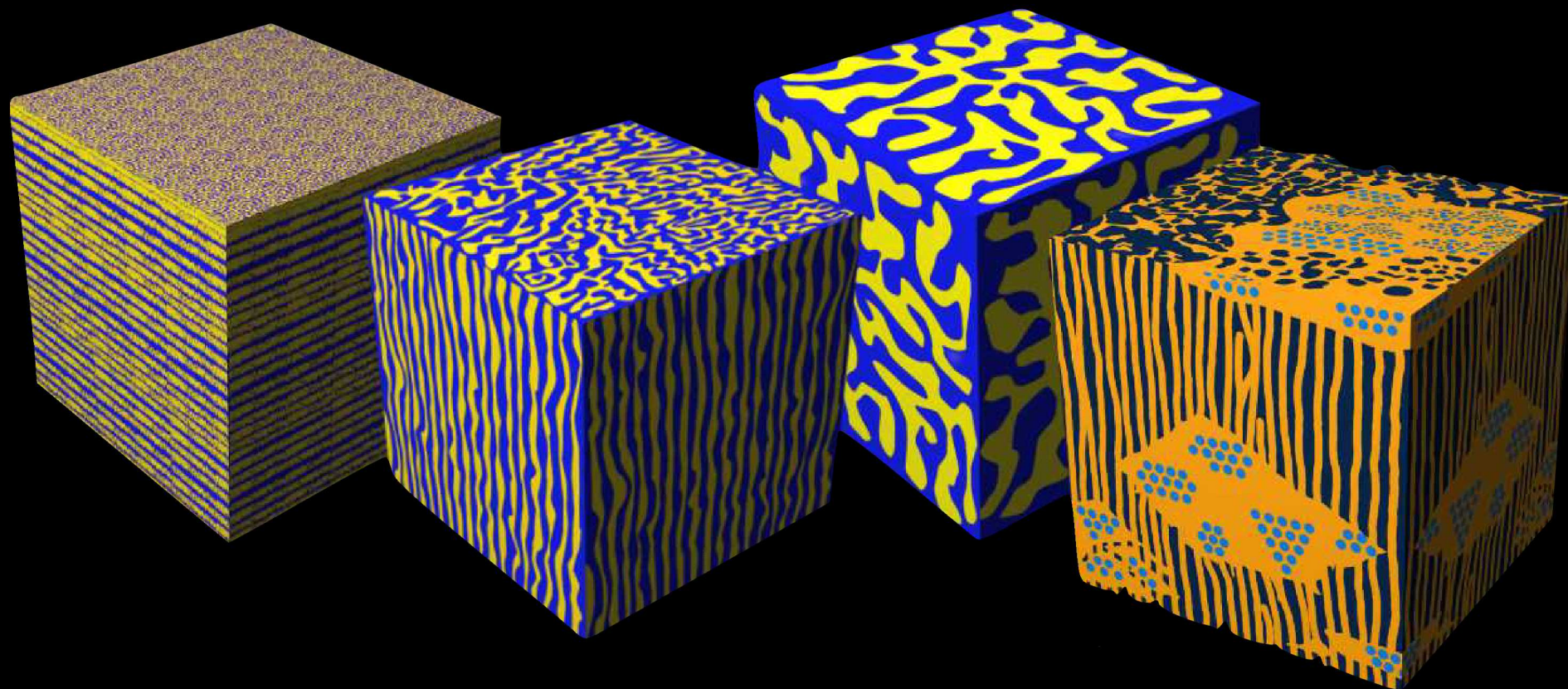
RT deposition  
+  
Annealing



Annealing

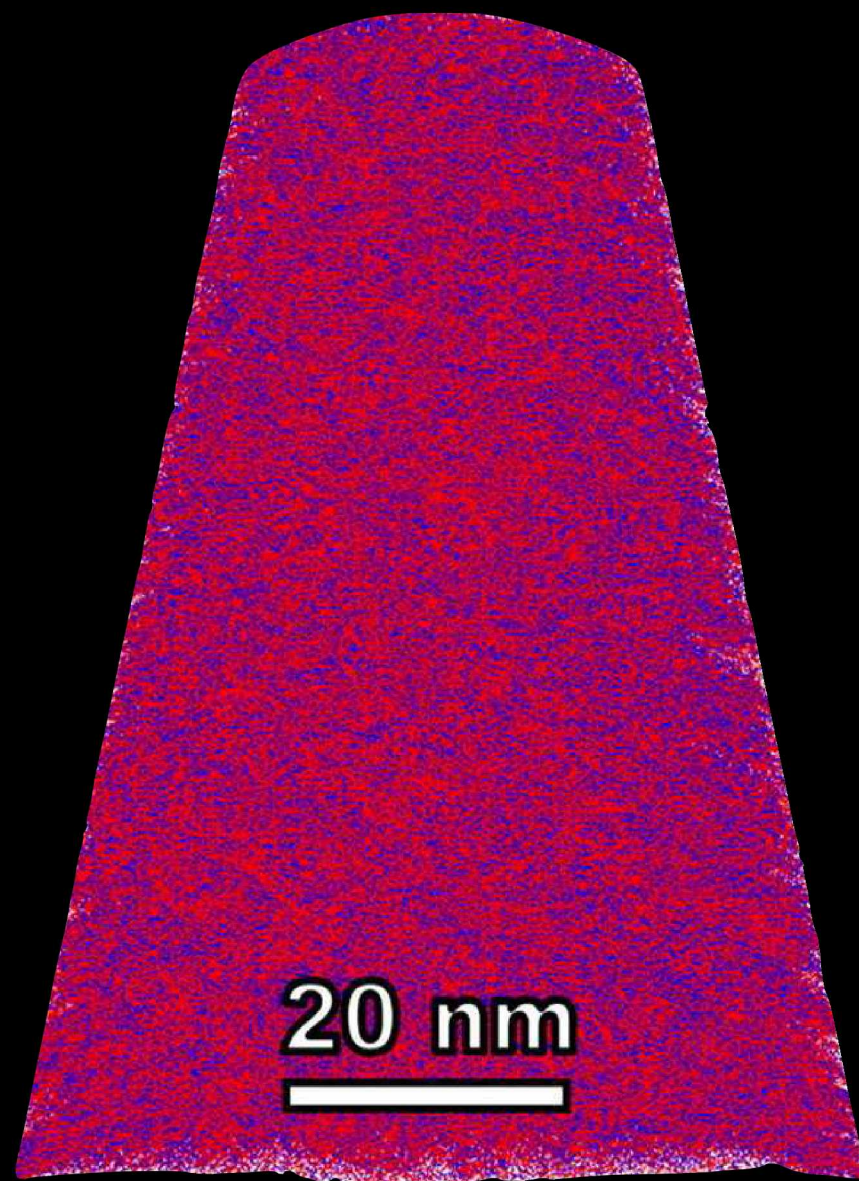


Heating  
during  
deposition

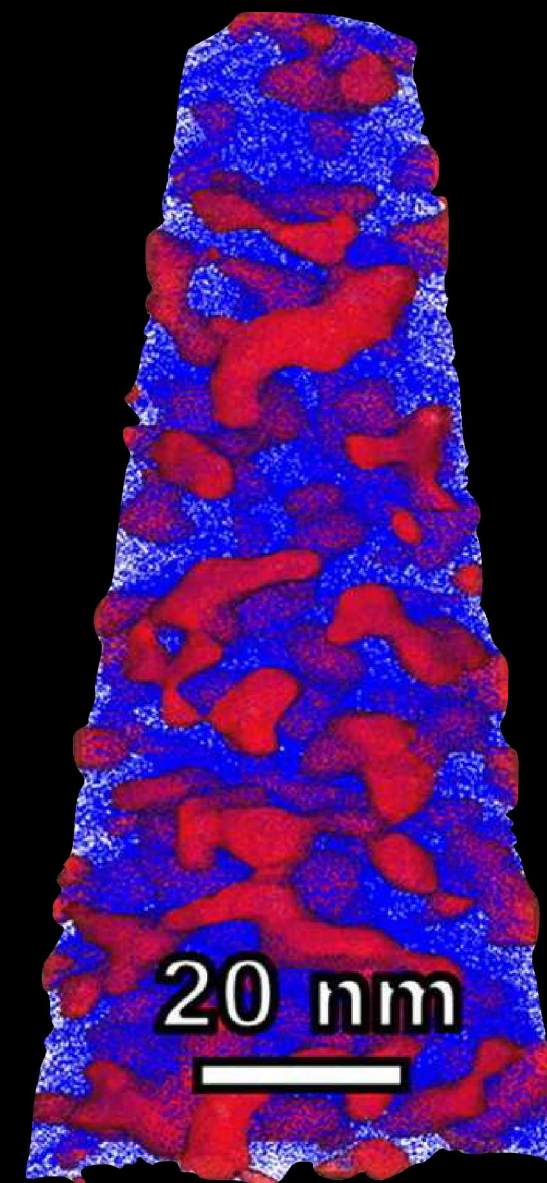




# EXAMPLE 1: PHASE SEPARATION IN CU-TA DUE TO CO-DEPOSITION FOLLOWED BY ANNEALING

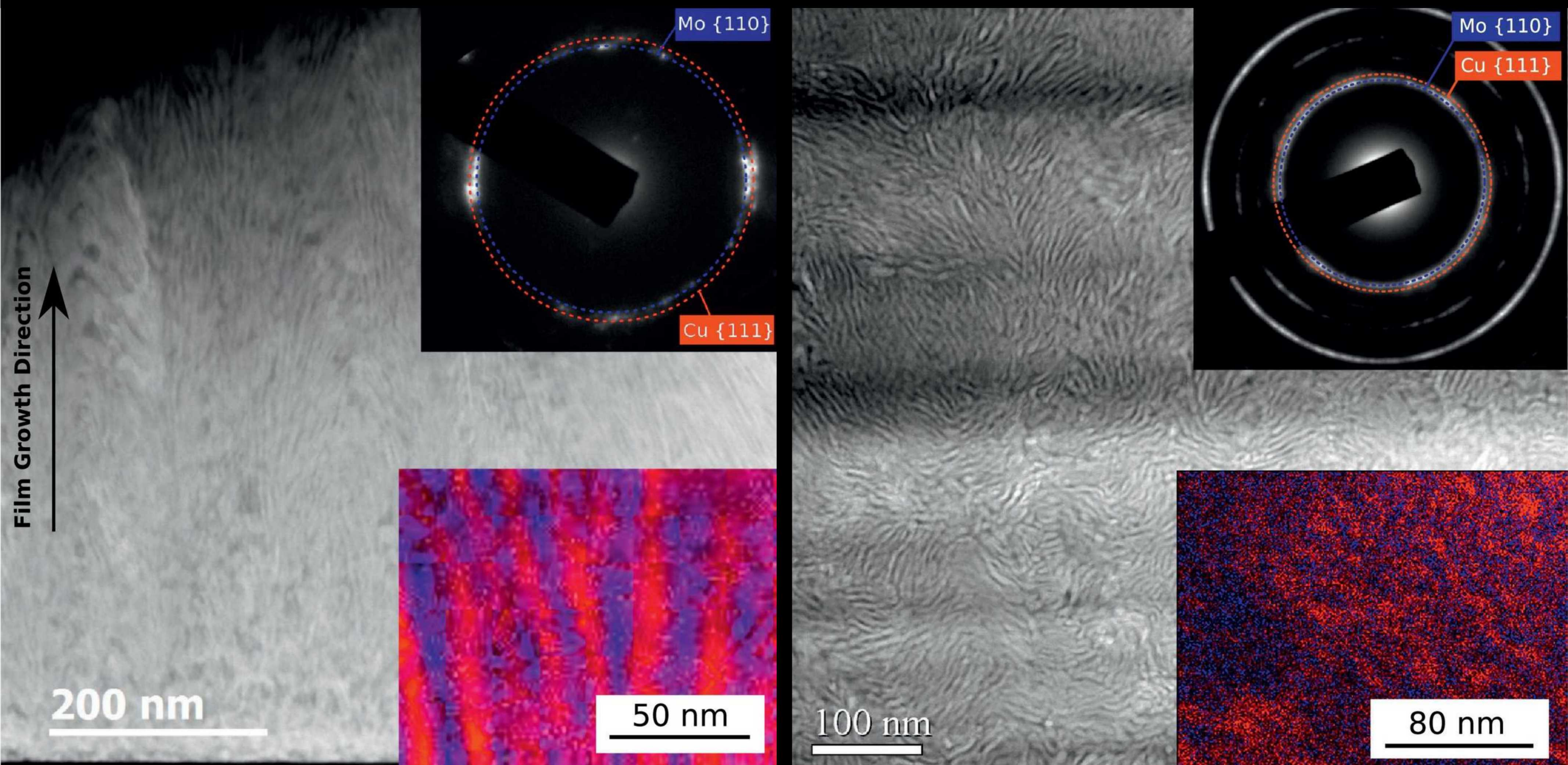


Annealing at  
400 C  
for 30 min





# EXAMPLE 2: PHASE SEPARATION IN CU-MO BY CHANGING THE DEPOSITION TEMPERATURE AND FLUX





# THERE ARE MULTIPLE VARIABLES AFFECTING THE RESULTING MICROSTRUCTURE

Deposition  
rate  
(target  
power)

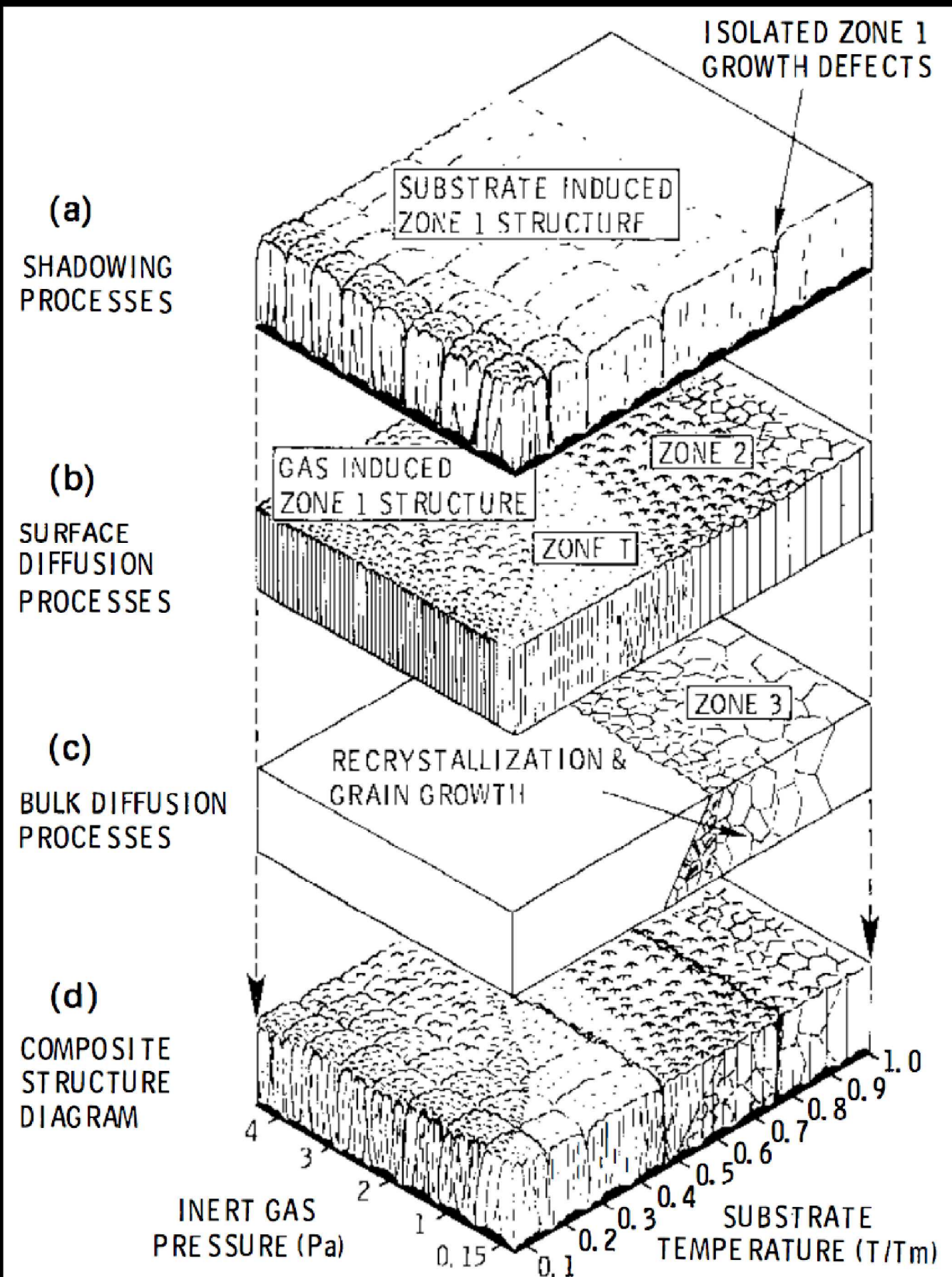
Residual  
elastic  
fields

Substrate  
bias

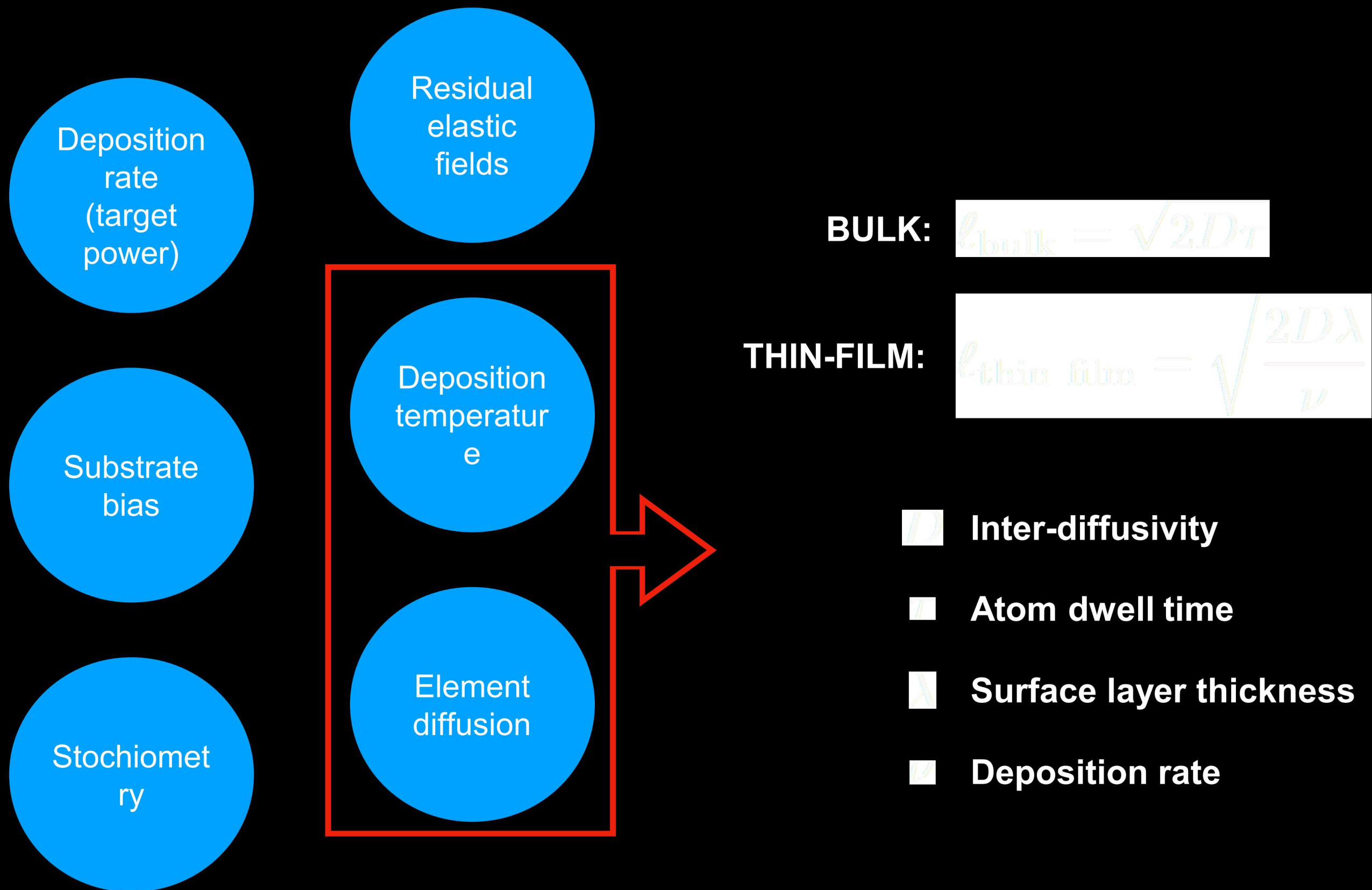
Deposition  
temperature

Stoichiometry

Element  
diffusion



# THE CHARACTERISTIC SIZE IS GOVERNED BY THE COMPETITION BETWEEN BULK AND SURFACE ORDERING





# THE SYNTHESIS CHALLENGE

- **BROAD RANGE OF DEPOSITION CONDITIONS**

- TARGET POWER
- TEMPERATURE
- SHADOWING

- **BROAD RANGE OF SPECIES**

- SURFACE VS. BULK DIFFUSION

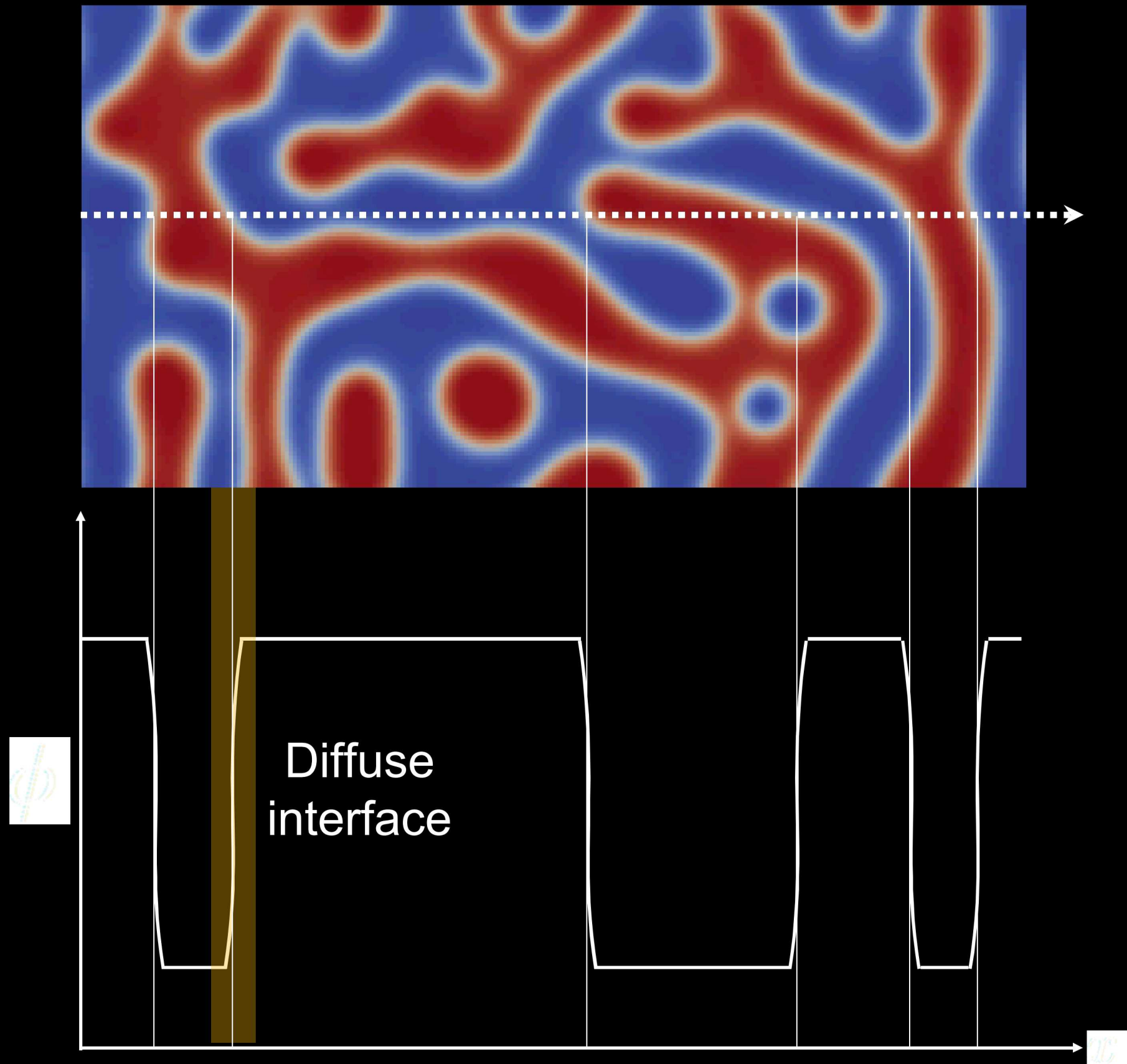
- **BEYOND SINGLE PHASE SYSTEMS**

- COMPETITION IN PHASE ORDERING
- ELASTIC MISMATCH





# PHASE FIELD 101: MODELING MICROSTRUCTURE EVOLUTION





# PHASE FIELD 101: MODELING MICROSTRUCTURE EVOLUTION

$$I' = \int \left[ f(\eta_1, \dots, \eta_p, \underbrace{c_1, \dots, c_p}_{\text{conserved}}) + \sum_{i=1}^n \alpha_i (\nabla c_i)^2 + \sum_{i,j=1}^3 \sum_{k=1}^p \beta_{ij} \nabla_i \eta_k \nabla_j \eta_k \right] dS$$

**Allen-Cahn:**  
Non-conserved

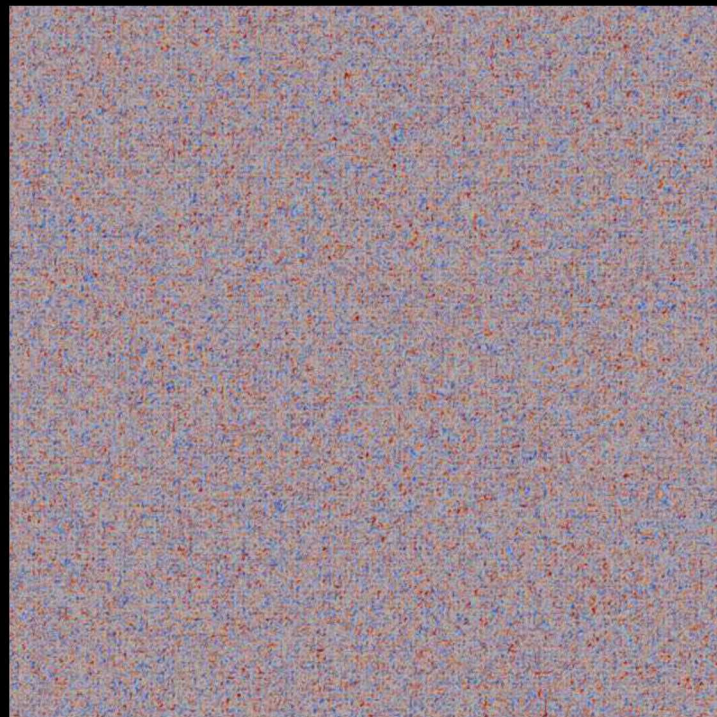
$$\frac{\partial \eta_p}{\partial t} = -M_{pq} \frac{\delta I'}{\delta \eta_q}$$

**Cahn-Hilliard:**  
Conserved

$$\frac{\partial c_i}{\partial t} = \nabla \cdot \left( M_{ij} \nabla \frac{\delta I'}{\delta c_j} \right)$$

Grain growth

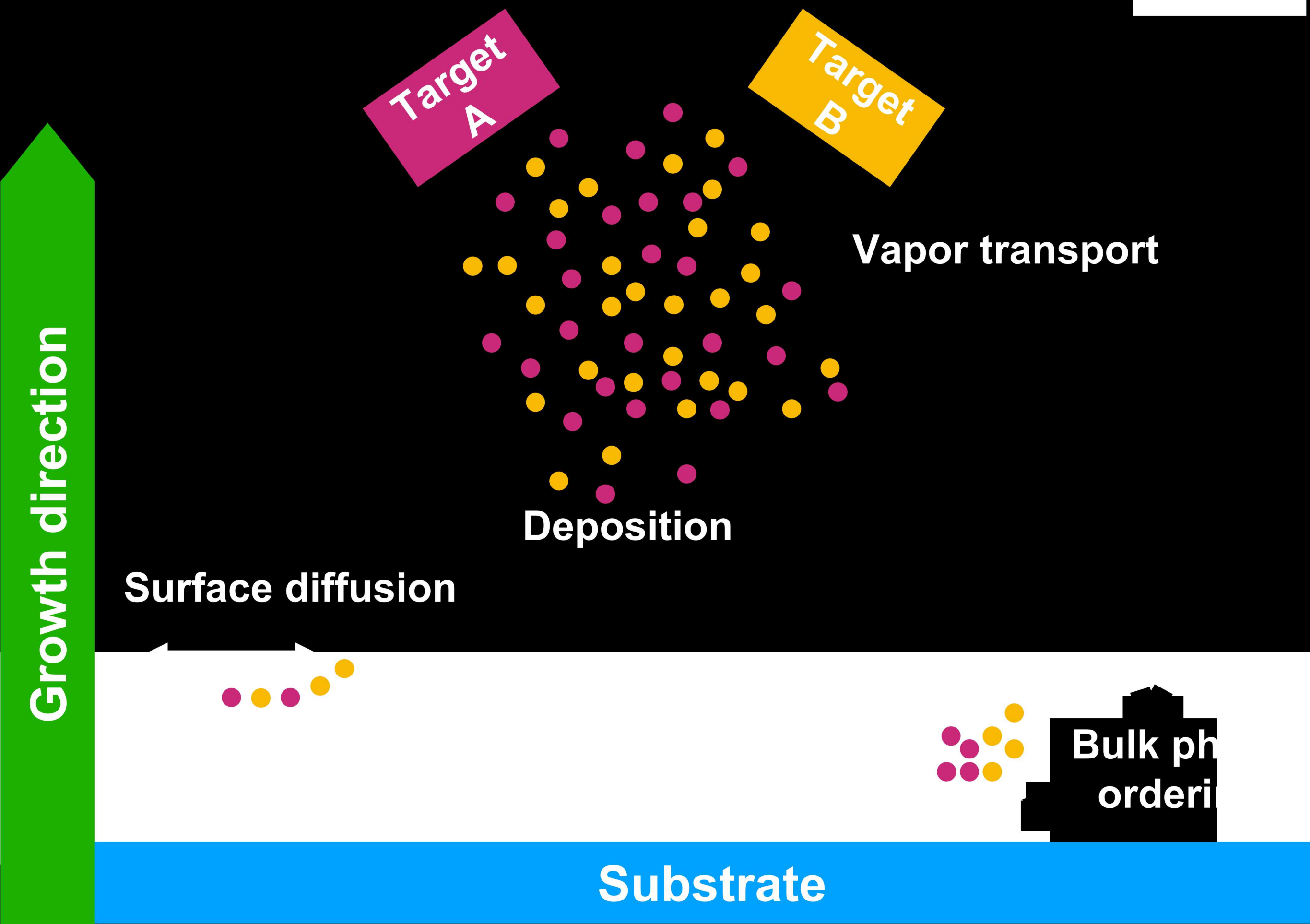
Spinodal  
decomposition



Solidification



# MODELING VAPOR DEPOSITION WITH PHASE FIELD





# MODELING VAPOR DEPOSITION WITH PHASE FIELD

$$F = \int \left[ f_\phi + \frac{\kappa_\phi^2}{2} (\nabla \phi)^2 + s(\phi) \left( f_c + \frac{\kappa_c^2}{2} (\nabla c)^2 \right) \right] d\Omega$$

Target  
A

Target  
B

$$\frac{\partial \rho}{\partial t} = \nabla \cdot (D(\rho) \nabla \rho) - \nabla \cdot (\rho \vec{u}) + S(\vec{n})$$

Vapor transport

Vapor density (background pressure)  
Deposition velocity (sputtering power)  
Shadowing effect

$$\frac{\partial \phi}{\partial t} = \nabla \cdot \left( M(\phi) \nabla \frac{\delta F}{\delta \phi} \right) + S(\vec{n})$$

Deposition

Surface diffusion

$$\phi = -1$$

$$\frac{\partial c}{\partial t} = \nabla \cdot \left( D(c) \nabla \frac{\delta F}{\delta c} \right)$$

$$M_c(\phi, c) = M^{\text{Bulk}} + M^{\text{Surf}}$$



$$\phi = 1$$

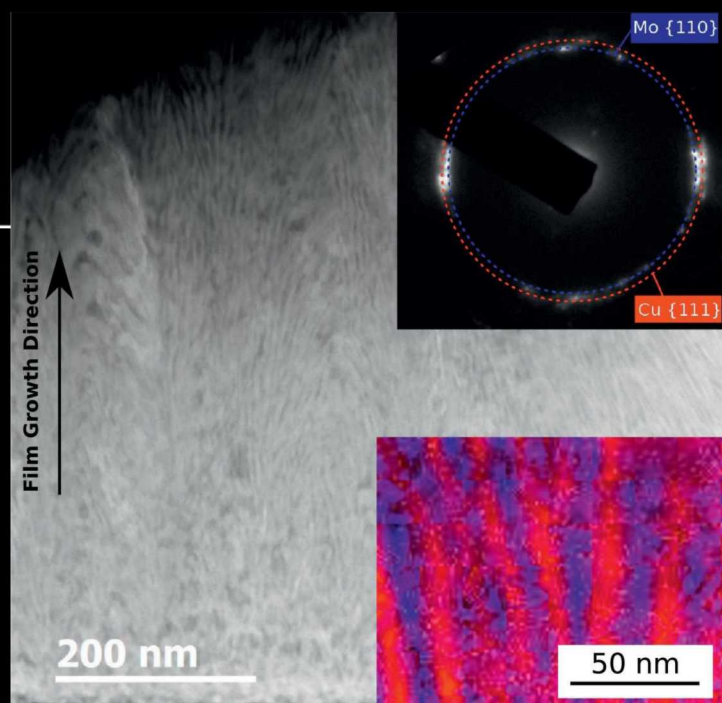


Bulk phase  
ordering

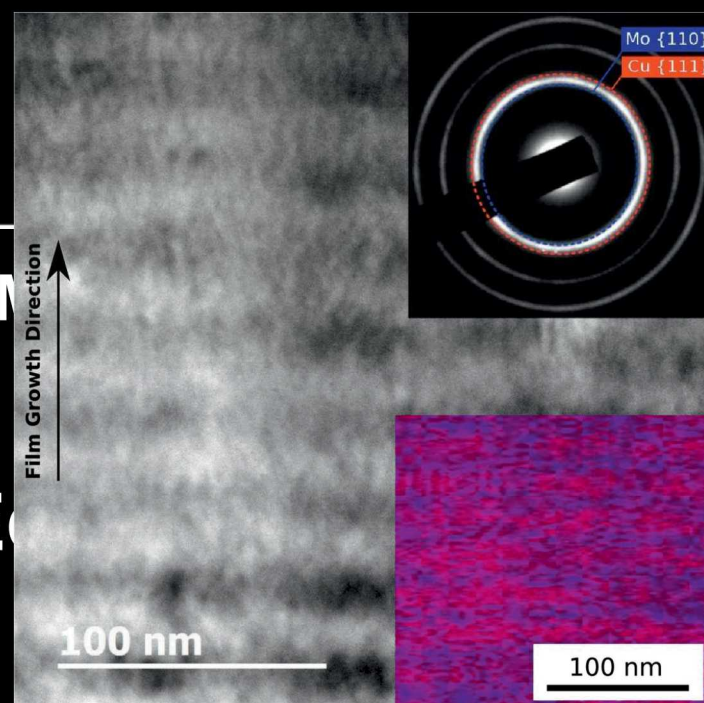
Substrate

# SYNTHESIS ROUTES ENABLE ACCESS TO AT LEAST FOUR CLASSES OF CONCENTRATION MODULATIONS

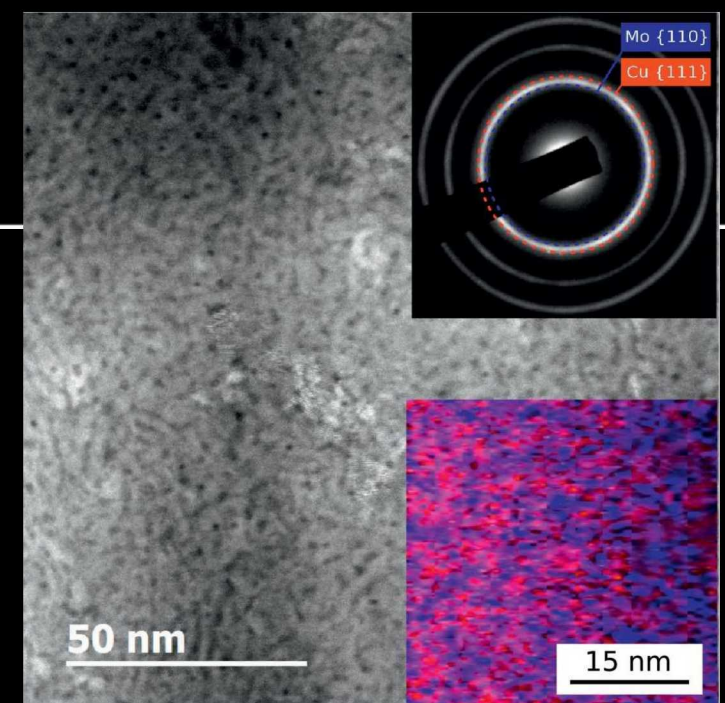
Lateral  
(LCM)



Vertical  
(VCM)



Random  
(RCM)





# SYNTHESIS ROUTES ENABLE ACCESS TO AT LEAST FOUR CLASSES OF CONCENTRATION MODULATIONS

**Raft-like lateral structure**

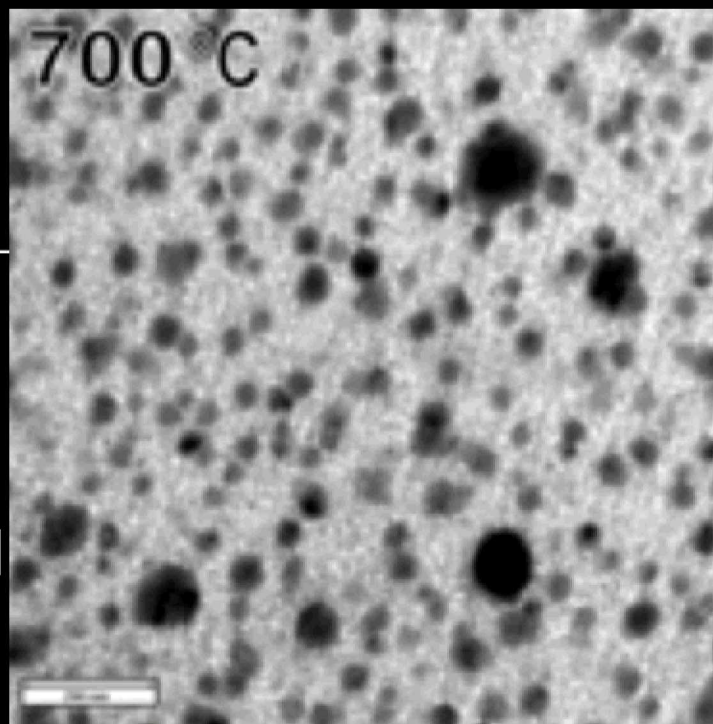
**Nanoprecipitates  
(NPCM)**

**Hybrid  
(NPCM/LCM)**

**Slow deposition rate**

**High deposition rate**

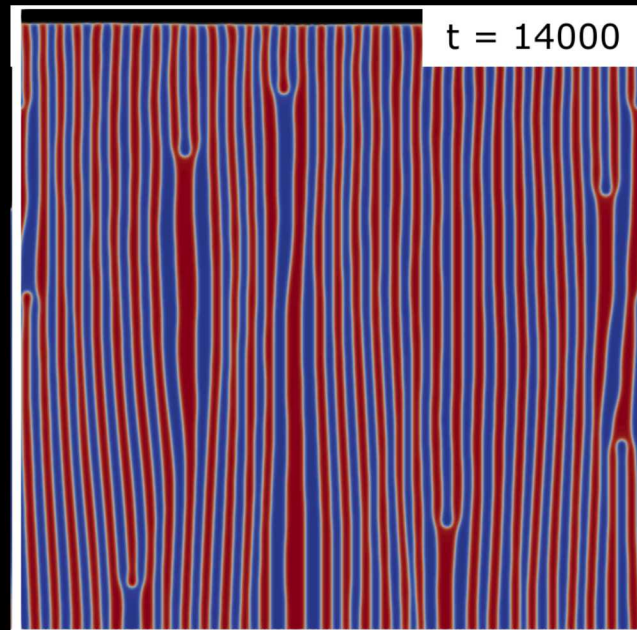
**UN** **TION**





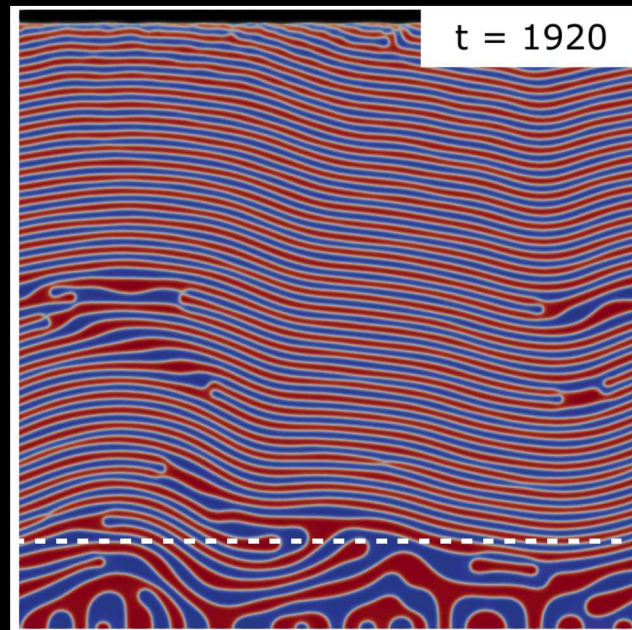
# THE FORMATION AND EVOLUTION OF THESE MORPHOLOGIES STEM FROM COMPLEX COMPETITIONS

LCM



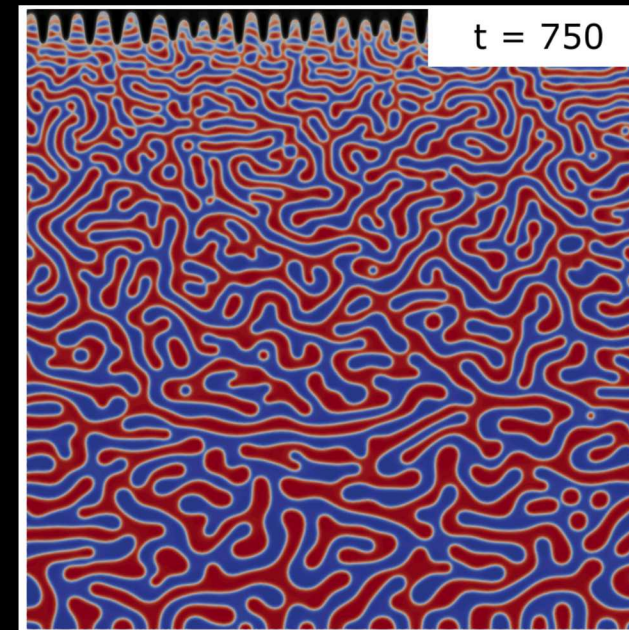
- Surface and bulk ordering much faster than slow deposition
- Deposited material diffuses further and faster along surface before being buried by “next” layer of deposited material

VCM



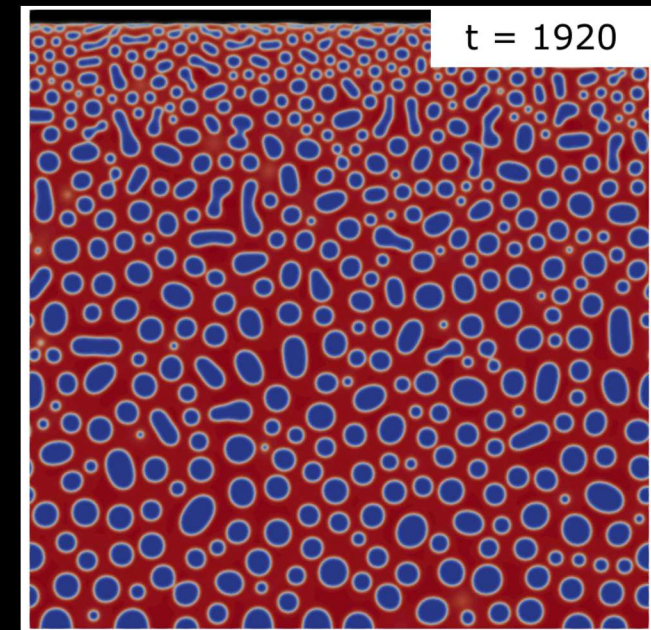
- Critical thin thickness above which interfacial contribution is energetically favored
- “Frozen” bulk approximation

RCM



- Rapid transition to “bulk” regime
- Classical spinodal decomposition
- Formation of hillocks and surface roughness due to continuous perturbation of free surface

NPCM



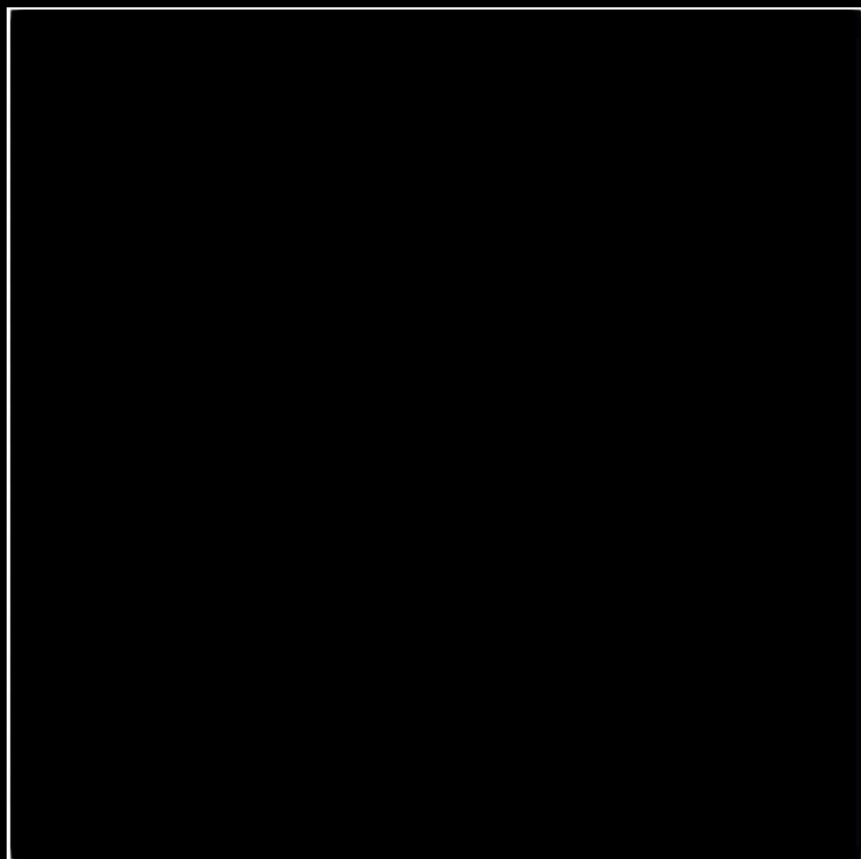
- Interparticle diffusion interactions (Ostwald ripening)
- Broader range of deposition conditions for unequal phase fraction



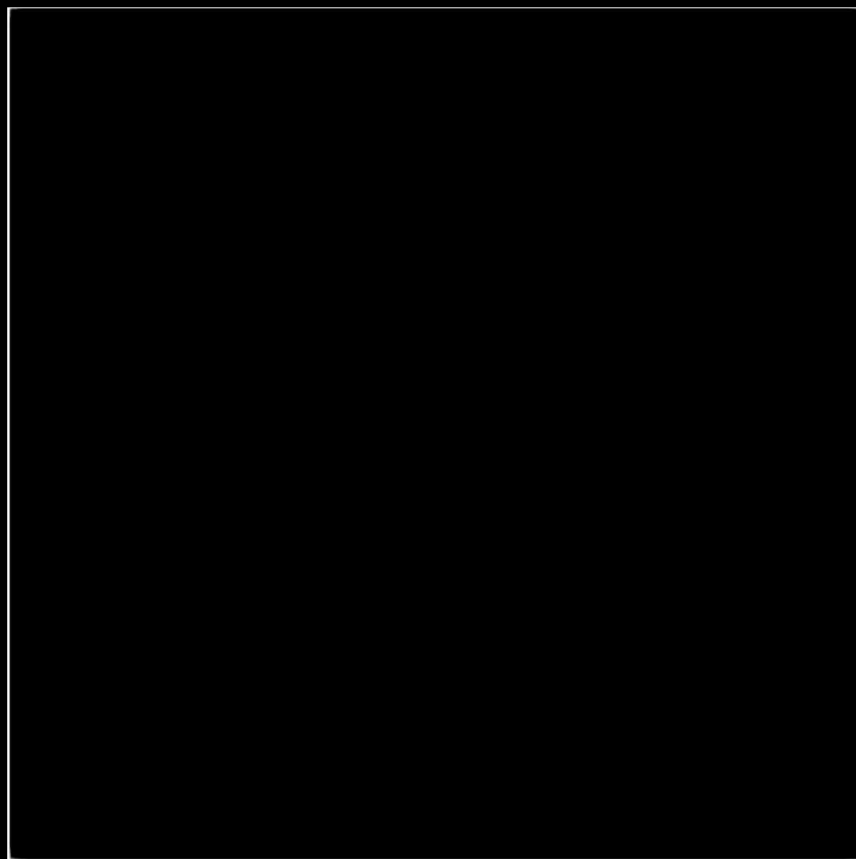
# PHASE KINETICS HAS AN IMPACT ON THE RESULTING CONCENTRATION MODULATION



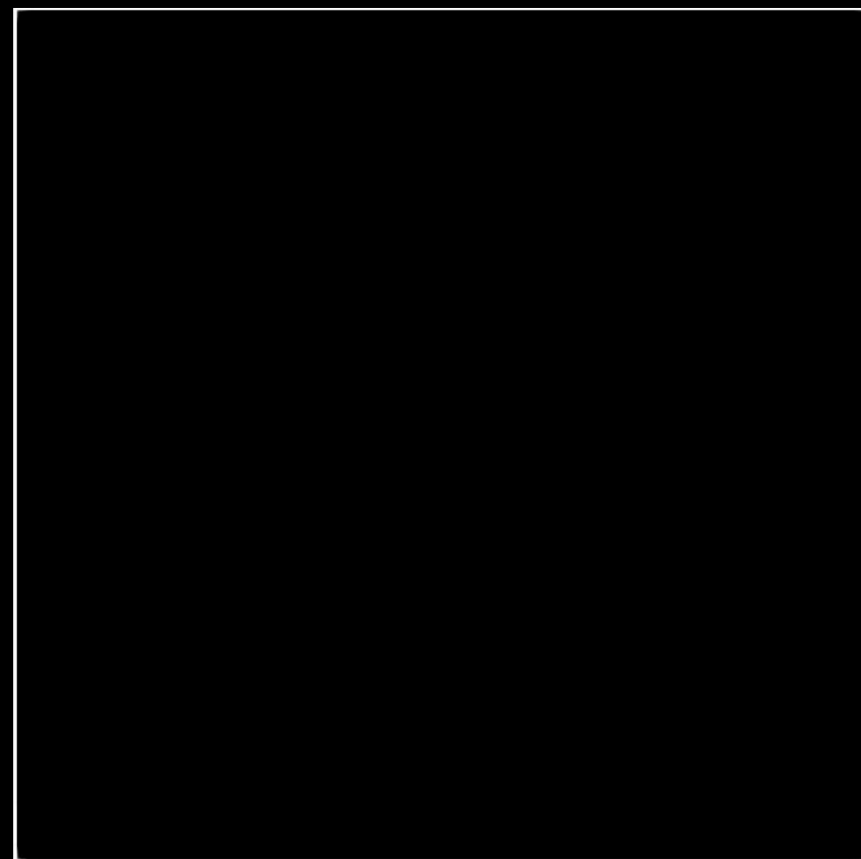
**Majority species  
with faster kinetics**



**Equivalent kinetics  
between species**



**Minority species  
with faster kinetics**



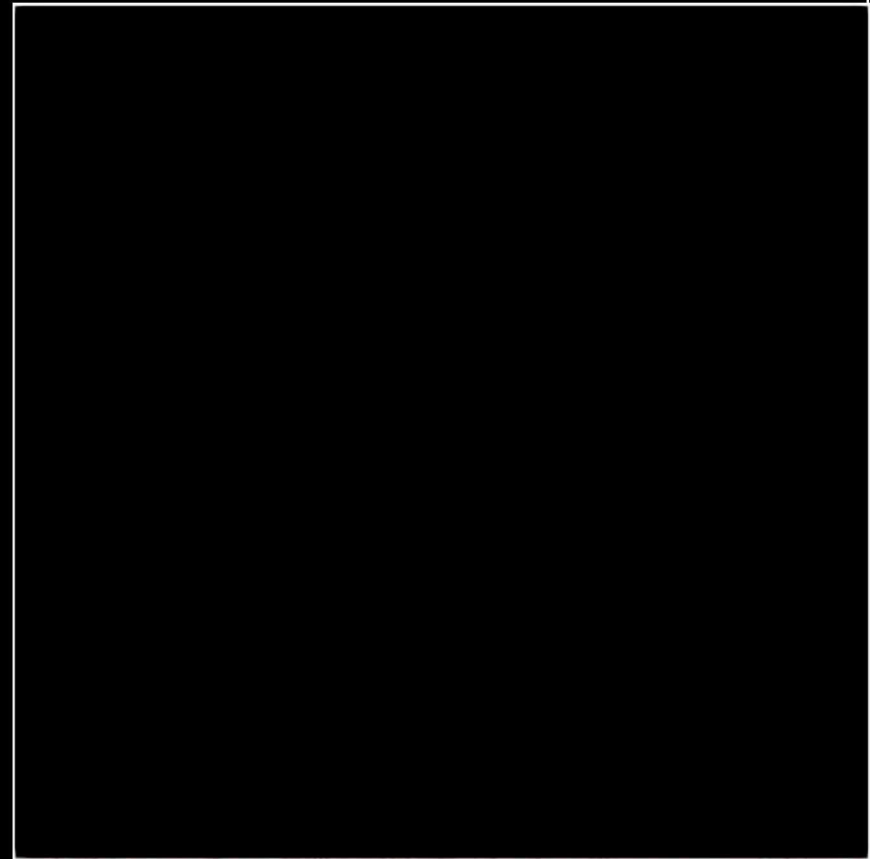
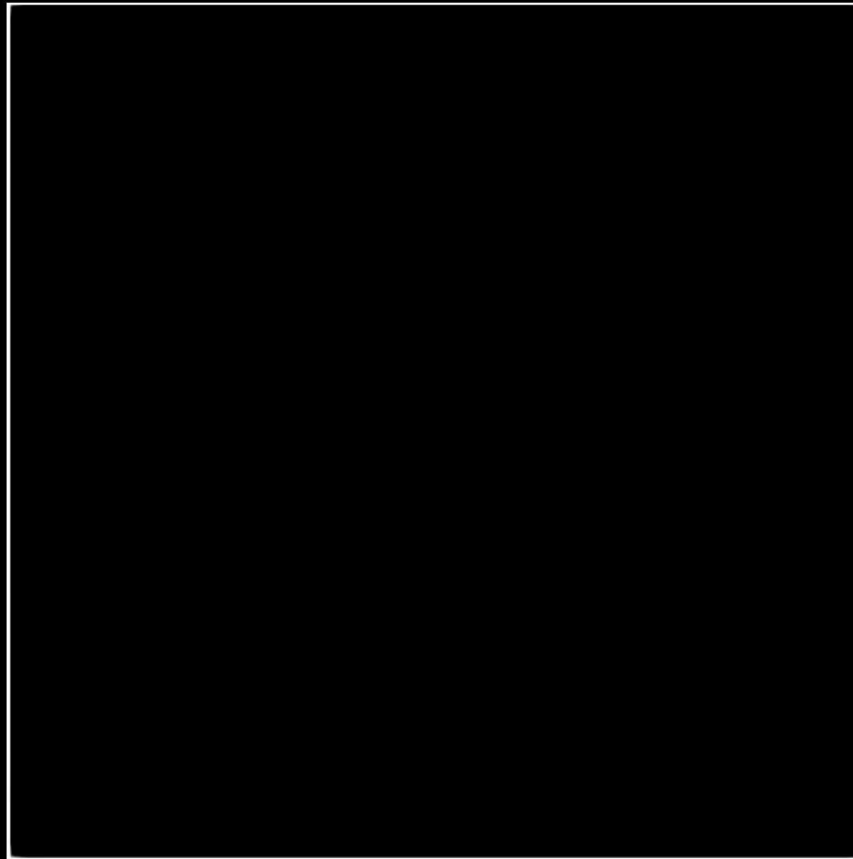
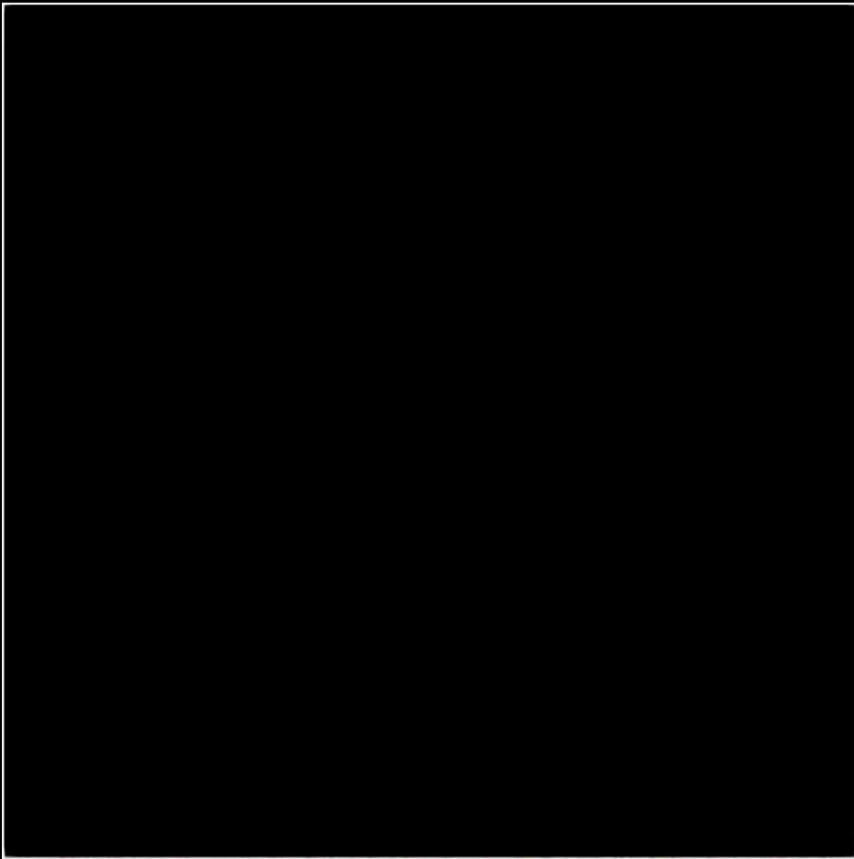
# ELASTIC EFFECTS CAN HAVE AN IMPACT ON THE SIZE AND SHAPE OF THE PHASE ORDERING



**Majority species is soft**

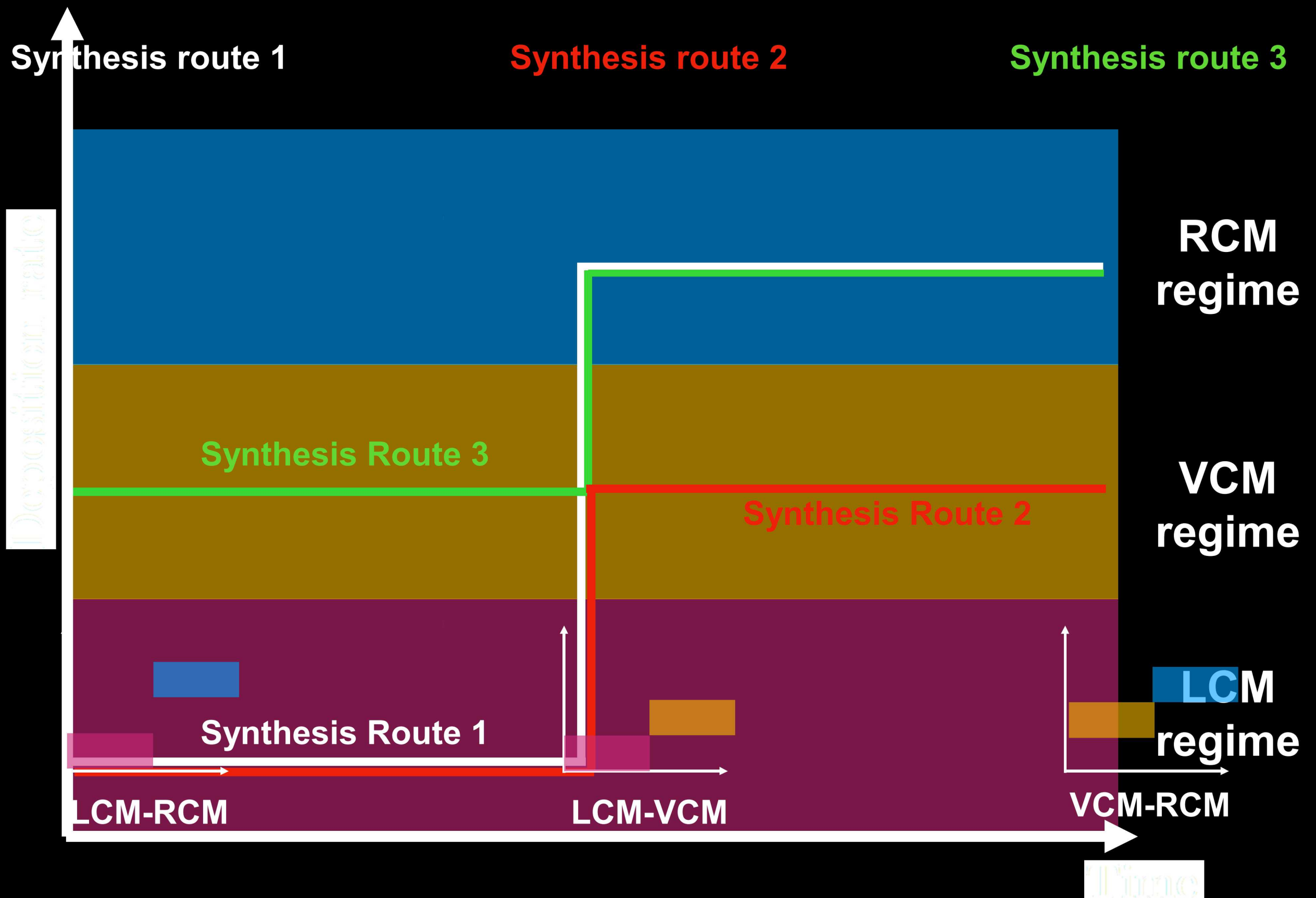
**No elasticity**

**Majority species is hard**



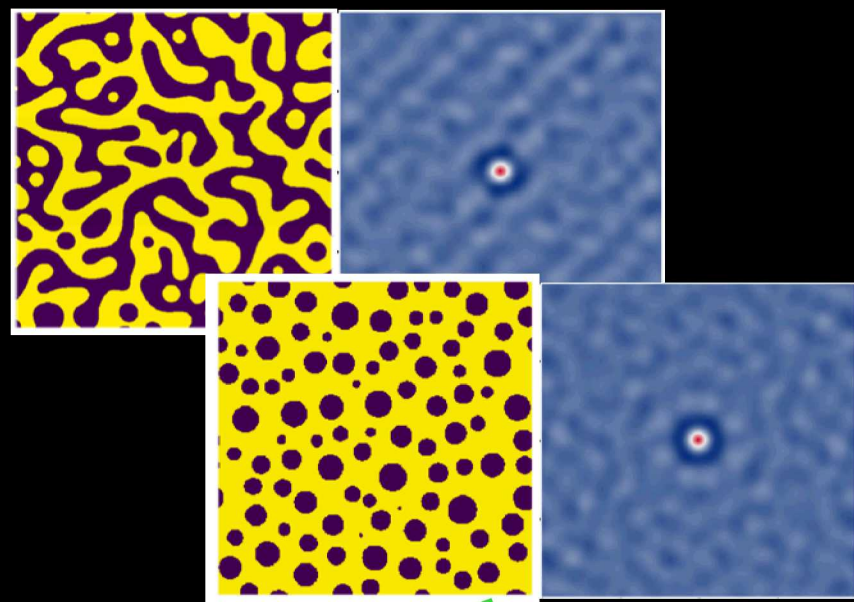


# GOING BEYOND SIMPLE SYNTHESIS ROUTES... MULTI-MODULATION MORPHOLOGIES

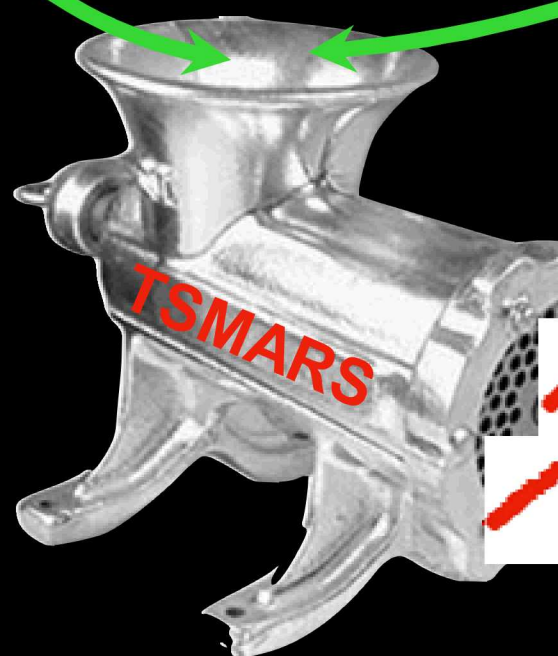
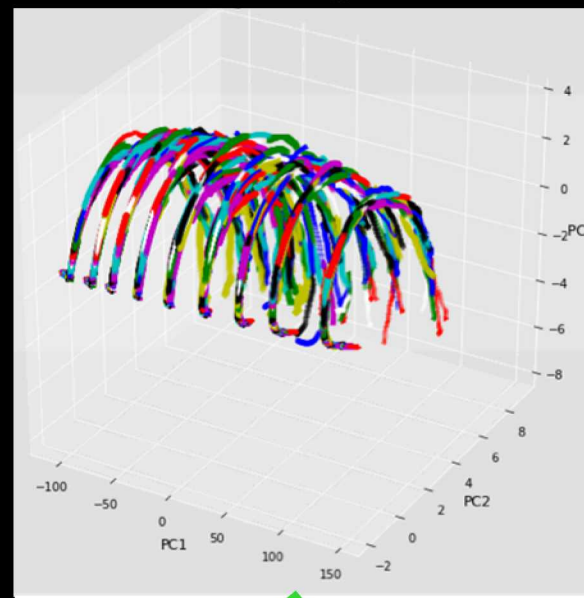


# GOING BEYOND PHASE FIELD MODELING... MACHINE-LEARNED ENABLED PROCESS-STRUCTURE PREDICTIONS

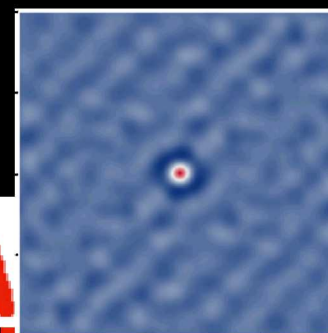
Dimensionality reduction



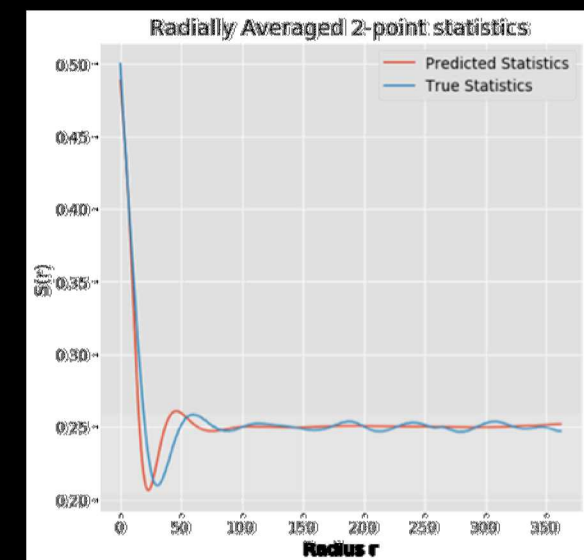
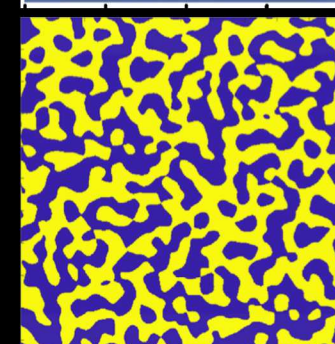
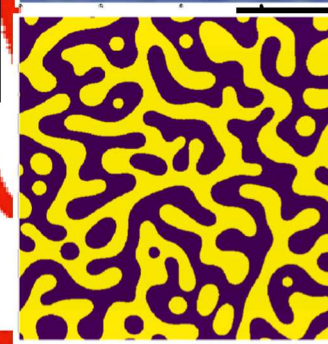
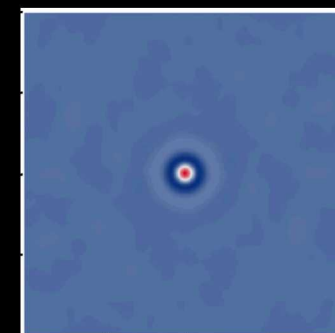
Training data



True



Predicted







- **Modeling of the growth of bicontinuous nanocomposites thin-films during PVD**
  - Generalized phase field model.
    - MEMPHIS: CINT user phase-field capability
  - Transport, surface diffusion, chemo-mechanical coupling during phase ordering
- **Insights into competing formation mechanisms**
  - Lateral, vertical, random, nanoprecipitate morphologies through specific combinations of deposition rate, phase fraction and phase properties
  - Guiding the choice of alloy species and deposition conditions to obtain specific nanostructured morphologies
  - Advanced regression/machine learning models to reverse engineering deposition conditions





# BIG SCIENCE AT THE NANOSCALE

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CINT is a user facility providing cutting-edge nanoscience and

nanotechnology capabilities to the research community.

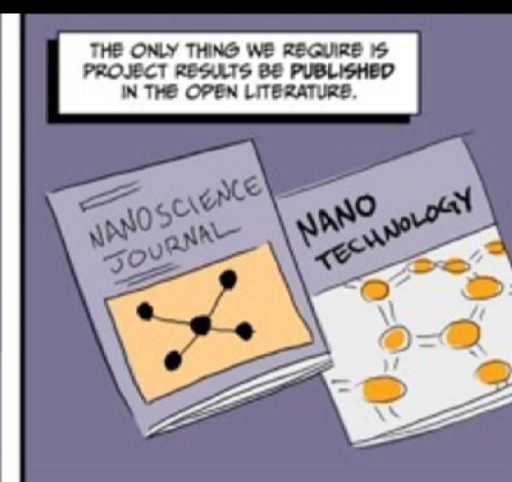
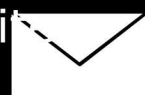
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